

**AMENDMENTS TO THE CLAIMS:**

This listing of claims will replace all prior versions, and listings, of claims in the application:

1. (Currently Amended) A method for manufacturing a liquid crystal display device, comprising the steps of:

forming a layer including a photocatalytic substance over a substrate;  
forming a gate [[first]] electrode over the layer including the photocatalytic substance a substrate;  
forming a first insulating film to cover the gate [[first]] electrode;  
forming a pixel electrode over the first insulating film;  
forming a first semiconductor layer over the first insulating film and the pixel electrode;  
forming a second insulating film over the first semiconductor layer to overlap the gate [[first]] electrode;  
forming a an-n-type second semiconductor layer to cover the second insulating film;  
patterning the first and second semiconductor layers into an island shape;  
forming source and drain wirings a second and a third electrodes over the second semiconductor layer; and  
etching the second semiconductor layer using the source and drain wirings second and the third electrode as a mask to be separated; and  
forming a fourth electrode to be in contact with the third electrode,  
wherein at least one of the gate electrode, the pixel electrode, and the source and drain wirings first electrode, the second electrode, the third electrode and the fourth electrode is formed by a droplet discharge method.

2. (Currently Amended) A method for manufacturing a liquid crystal display device, comprising the steps of:

forming a layer including a photocatalytic substance over a substrate;  
forming a gate [[first]] electrode over the layer including the photocatalytic substance a substrate;  
forming a first insulating film to cover the gate [[first]] electrode;  
forming a first semiconductor layer over the first insulating film;

forming a second insulating film over the first semiconductor layer to overlap the gate [[first]] electrode;

forming a ~~an n-type~~ second semiconductor layer to cover the second insulating film;

patterning the first and second semiconductor layers into an island shape;

forming source and drain wirings ~~a second and a third electrodes~~ over the second semiconductor layer;

etching the second semiconductor layer using the source and drain wirings ~~second and the third electrode~~ as a mask ~~to be separated~~;

forming a third insulating film over the source and drain wirings ~~second electrode, the third electrode~~ and the first insulating film;

forming an opening in third insulating film; and

forming a pixel ~~fourth~~ electrode over the third insulating film,

wherein the pixel ~~fourth~~ electrode is electrically connected with one of the source and drain wirings ~~third electrode~~ through the opening, and

wherein at least one of the gate electrode, the source and drain wirings, and the pixel electrode ~~first electrode, the second electrode, the third electrode and the fourth electrode~~ is formed by a droplet discharge method.

3. (Canceled)

4. (Currently Amended) A method for manufacturing a liquid crystal display device, comprising the steps of:

forming a layer including a photocatalytic substance over a substrate;

forming a gate [[first]] electrode over the layer including the photocatalytic substance ~~a substrate having an insulating surface~~;

forming a first insulating film to cover the gate [[first]] electrode;

forming a pixel ~~second~~ electrode over the first insulating film;

forming a first semiconductor layer over the first insulating film and the pixel ~~second~~ electrode;

forming a second insulating film over the first semiconductor layer to overlap the gate [[first]] electrode;

forming a ~~an n-type~~ second semiconductor layer to cover the second insulating film;

patterning the first and the second semiconductor layers into an island shape;  
forming source and drain wirings ~~a third and a fourth electrodes~~ over the second semiconductor layer; [[and]]

etching the second semiconductor layer using the source and drain wirings ~~third and the fourth electrodes~~ as a mask ~~to be separated;~~ and

forming a third insulating film over the source and drain wirings and the pixel electrode,

wherein the pixel ~~second~~ electrode is electrically connected with one of the source and drain wirings ~~fourth electrode~~, and

wherein at least one of the gate electrode, the pixel electrode, and the source and drain wirings ~~first electrode, the second electrode, the third electrode and the fourth electrode~~ is formed by a droplet discharge method.

5. – 12. (Canceled)

13. (New) The method for manufacturing a liquid crystal display device according to claim 1, wherein the layer including the photocatalytic substance is a TiO<sub>2</sub> layer.

14. (New) The method for manufacturing a liquid crystal display device according to claim 1, wherein the layer including the photocatalytic substance has hydrophilic property.

15. (New) The method for manufacturing a liquid crystal display device according to claim 2, wherein the layer including the photocatalytic substance is a TiO<sub>2</sub> layer.

16. (New) The method for manufacturing a liquid crystal display device according to claim 2, wherein the layer including the photocatalytic substance has hydrophilic property.

17. (New) The method for manufacturing a liquid crystal display device according to claim 4, wherein the layer including the photocatalytic substance is a TiO<sub>2</sub> layer.

18. (New) The method for manufacturing a liquid crystal display device according to claim 4, wherein the layer including the photocatalytic substance has hydrophilic property.